

CLAIMS

Therefore, having thus described the invention, at least the following is claimed:

- 1 1. A polymer, comprising:
2 a photodefinable polymer including a sacrificial polymer and a
3 photoinitiator.

- 1 2. The polymer of claim 1, wherein the photoinitiator is a negative tone
2 photoinitiator.

- 1 3. The polymer of claim 1, wherein the photoinitiator is a positive tone
2 photoinitiator.

- 1 4. The polymer of claim 1, wherein the sacrificial polymer is selected from
2 polynorbornenes, polycarbonates, polyethers, polyesters, functionalized
3 compounds of each, and combinations thereof.

- 1 5. The polymer of claim 1, wherein the sacrificial polymer includes
2 polynorbornene.

- 1 6. The polymer of claim 3, wherein the polynorbornene includes alkenyl-
2 substituted norbornene.

- 1 7. The polymer of claim 1, wherein the photoinitiator is a free radical generators.

- 1 8. The polymer of claim 1, wherein the photoinitiator is selected from, bis(2,4,6-
2 trimethylbenzoyl)-phenylphosphineoxide, 2-benzyl-2-dimethylamino-1-(4-
3 morpholinophenyl)-butanone-1, 2,2-dimethoxy-1,2-diphenylethan-1-one, 2-
4 methyl-1[4-(methylthio)- phenyl]-2-morpholinopropan-1-one, 2-methyl-4'-
5 (methylthio)-2-morpholino-propionophenone, benzoin ethyl ether, and 2,2'-
6 dimethoxy-2-phenyl-acetophenone, and combinations thereof.

- 1 9. The polymer of claim 1, wherein the photoinitiator is selected from, bis(2,4,6-
2 trimethylbenzoyl)-phenylphosphineoxide and 2-benzyl-2-dimethylamino-1-(4-
3 morpholinophenyl)-butanone-1.
- 1 10. The polymer of claim 1, wherein the sacrificial polymer is about 1 to 30% by
2 weight percent of the photodefinable polymer, wherein the photoinitiator is
3 from about 0.5 to 5% by weight of the photodefinable polymer, wherein the
4 solvent is about 65% to 99% by weight percent of the photodefinable polymer.
- 1 11. A method for fabricating a structure, comprising:
2 disposing a photodefinable polymer onto a surface, wherein the
3 photodefinable polymer includes a sacrificial polymer and a photoinitiator
4 selected from a negative tone photoinitiator and a positive tone photoinitiator;
5 disposing a gray scale photomask onto the photodefinable polymer,
6 wherein the gray scale photomask encodes an optical density profile defining a
7 three-dimensional structure to be formed from the photodefinable polymer;
8 exposing the photodefinable polymer through the gray scale photomask
9 to optical energy; and
10 removing portions of the photodefinable polymer to form the three-
11 dimensional structure of cross-linked photodefinable polymer.
- 1 12. The method of claim 11, wherein removing includes:
2 removing unexposed portions of the photodefinable polymer to form
3 the three-dimensional structure.
- 1 13. The method of claim 11, wherein removing includes:
2 removing exposed portions of the photodefinable polymer to form the
3 three-dimensional structure.
- 1 14. The method of claim 11, further comprising:
2 disposing an overcoat layer onto the three-dimensional structure; and
3 decomposing the photodefinable polymer, thermally, to form a three-
4 dimensional air-region.

- 1 15. The method of claim 14, wherein decomposing includes:
2 maintaining a constant rate of decomposition as a function of time.
- 1 16. The method of claim 14, wherein decomposing includes:
2 maintaining a constant rate of mass loss of the photodefinable polymer.
- 1 17. The method of claim 14, wherein decomposing includes:
2 heating the structure according to the thermal decomposition profile
3 expression
4
$$T = \frac{E_a}{R} \left[\ln \frac{A(1-rt)^n}{r} \right]^{-1}$$

5 where R is the universal gas constant, t is time, n is the overall order of
6 decomposition reaction, r the desired polymer decomposition rate, A is the
7 Arrhenius pre-exponential factor, and E_a is the activation energy of the
8 decomposition reaction.
- 1 18. The method of claim 11, wherein the three-dimensional structure has a
2 spatially-varying height.
- 1 19. A structure, comprising the three-dimensional structure formed using the
2 method of claim 11.
- 1 20. A structure, comprising the three-dimensional air-region formed using the
2 method of claim 14.
- 1 21. A structure, comprising the three-dimensional air-region formed using the
2 method of claim 15.
- 1 22. A structure, comprising the three-dimensional air-region formed using the
2 method of claim 17.

- 1 23. A method of decomposing a polymer, comprising:
 2 providing a structure having a substrate, an overcoat layer, and a
 3 polymer in a defined area within the overcoat layer;
 4 maintaining a constant rate of decomposition as a function of time;
 5 removing the polymer from the area to form an air-region in the
 6 defined area.
- 1 24. The method of claim 23, wherein maintaining includes:
 2 heating the structure according to the thermal decomposition profile
 3 expression
 4
$$T = \frac{E_a}{R} \left[\ln \frac{A(1-rt)^n}{r} \right]^{-1}$$

 5 where R is the universal gas constant, t is time, n is the overall order of
 6 decomposition reaction, r the desired polymer decomposition rate, A is the
 7 Arrhenius pre-exponential factor, and E_a is the activation energy of the
 8 decomposition reaction.
- 1 25. A structure, comprising:
 2 a substrate;
 3 an air-region area having a spatially-varying height; and
 4 an overcoat layer disposed onto a portion of the substrate and engaging
 5 a substantial portion of the air-region area.
- 1 26. The structure of claim 25, wherein the air-region area has a non-rectangular
 2 cross-section.
- 1 27. The structure of claim 25, wherein the air-region area has an asymmetrical
 2 cross-section.